Application No. 09/509,472



13. (Thrice Amended) A photomask in which a mask pattern has been formed by the patterning of the thin film formed on the transparent substrate of the photomask blank according to the invention in Claim 1.

REMARKS

Claims 1-30 are pending herein. By this Amendment, claims 6, 10 and 13 are amended to correct typographical errors in the Amendment filed January 22, 2002.

Should the Examiner believe that anything further would be desirable in order to place this application in better condition for allowance, the Examiner is invited to contact Applicants' undersigned representative at the telephone number listed below.

Respectfully submitted,

James A. Oliff Registration No. 27,075

David M. Lafkas Registration No. 50,424

JAO:DML/rxg

Attachment:

Appendix

Date: March 4, 2002

OLIFF & BERRIDGE, PLC P.O. Box 19928 Alexandria, Virginia 22320 Telephone: (703) 836-6400 DEPOSIT ACCOUNT USE
AUTHORIZATION
Please grant any extension
necessary for entry;
Charge any fee due to our
Deposit Account No. 15-0461

Application No. 09/509,472

Docket No. 105875

APPENDIX

Changes to Claims:

The following are marked-up versions of the amended claims:

- 6. (Thrice Amended) The photomask blank according to Claim 4, wherein the carbon content is 0 to 25 atomic% and the oxygen content is 0 to 75 70 atomic%.
- 10. (Thrice Amended) The photomask blank according to Claim 9, wherein the thin film has an oxygen content that continuously decreases and a carbon content that continuously increases from the thin film surface side to the transparent substrate side, nitrogen is contained in the nitride film in a relatively greater amount than the amount of nitrogen contained in the thin film, and the amount of the metal decreases as the amount of nitrogen in the nitride film increases.
- 13. (Thrice Amended) A photomask blank in which a mask pattern has been formed by the patterning of the thin film formed on the transparent substrate of the photomask blank according to the invention in Claim 1.